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Digest of Tech. Papers The 9th Conf. on Solid State Devices, Tokyo

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High Speed 4K Static RAM using DSAMOST's

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A high speed, fully static, 1024 word by 4 bit Random Access Memory has been 1) developed, using Diffusion Self-Aligned (DSA) MOS transistors as active devices.

The present RAM operates on a single power supply of 5 (± 1) volts without internal bias generator. Its typical performances are; access time 57nsec, cycle time 100nsec and operating power 520mW. The device was also confirmed to operate satisfactorily in the battery back up mode with 4.4mW ($V_{DD}=1.1$ V) power dissipation.

Figure I shows a cross section of the DSA ED MOS inverter integrated in the RAM. Silicon gate device structure with reduced dimensions was combined with the advanced local oxidation technique to realize the high speed operation of the RAM.

In DSA devices with less than 2 μm source-drain separation, gate oxide of about 800 Å thickness and source and drain regions of about 1 μm depth were used without any problems of short channel effects. Measured gain constant β magnitude is about 90 $\mu v/V$, for 10 μm gate width. The DSA MOST threshold voltage was tightly controlled within 1.0±0.1 volt by use of the refined ion-implantation technique. The ptype diffused layer for the channel stopper was vertically separated from the source and drain n^+ regions, as is shown in Fig.1. Together with the high resistive ($100\Omega cm$) substrate used, this devised isolation structure substantially reduced the junction capacitance leading to the high speed operation of the device.

In the load device, two types of load MOST's with different threshold voltage ($V_{\rm TL}$) values, which were adjusted by ion-implantation technique, were used to meet the high speed and low power requirement; one with $V_{\rm TL}=3$ volts for write driver and decoder, and the other with $V_{\rm TL}=0$ volt for decoder buffer and cell load.

The 1024 word by 4 bit static memory circuit was designed as follows: (1) Chip Enable (CE) circuit is made up of multiple connected ED inverters. CE circuit generates internal clock pulses. (2) Address, chip select and data buffers are flipflop type latch circuits. They are clocked by CE signals. (3) X,Y decoders are conventional NOR gates. Decoder buffers are push-pull circuits. As the decoder buffer, a push-pull circuit with 0 volt gate threshold load MOST was used. (4) Memory cell is the conventional 6 Tr. Cell. The load current is limited to under 1 µA. (5) For sense amplifiers, balanced differential amplifiers were used. (6) Data-in buffers and write drivers were constructed using the ED inverters and push-pull circuits. Figure 2 shows CE input and read-out signal waveforms. Figure 3 shows read access time V_{DD} dependency, and Figure 5 shows a DSA 4K static RAM chip microphotograph. Typical characteristics of 4K RAM are summarized on Table 1.

In conclusion, a high speed static 4K RAM with reasonable operating margin has been developed using DSA MOST's. The process technologies used are not critical ones and applicable to its production.

The authors are grateful to Drs. Y. Tarui and Y. Hayashi for valuable discussions. The authors also wish to thank Drs. Y. Matsukura, S. Asanabe, T. Okada and D. Shinoda for their continuous encouragement during this work, and H. Shibasaki for his assistance.

This work is contracted with the Agency of Industrial Science and Technology, MITI, as a part of the National Res. Dev. Prog., Pattern Information Processing System.

1) Y. Tarui etal., Proc. 1st Conf. Solid State Devices, Tokyo, 1969.

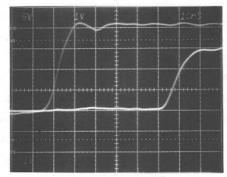


Fig. 2 Chip enable signal(a) and read-out signal (b) waveforms (VDD=5 V)

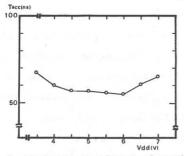
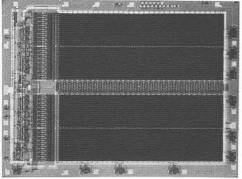
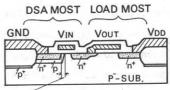


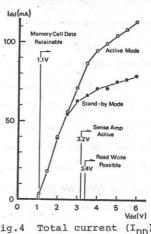
Fig.3 Read access time VDD dependency



A DSA 4K static RAM chip Fig.5 microphotograph



EFFECTIVE CHANNEL LENGTH Fig.1 A DSA ED inverter cross section



Total current (IDD) Fig. 4 V_{DD}dependency

N-channel Si gate, π planar DSA ED MOS, Technology: vertical separation I/O: I/O common and Tri-state output Pins: 22 pins 4.6 x 6.09 mm² n: 1024 word by 4 bit Chip size: Organization: fully static Cell structure: 6 Tr. static cell Power supply: 5 V single Power supply: Signal level: TTL compatible Read access time: 57 ns (25°C) 52 ns (0°C) Cycle time: 100 ns Power dissipation: 520 mW at active mode, 375 mW at stand-by mode

Table 1 4K RAM typical characteristics summary